EUROPEAN ORGANIZATION FOR NUCLEAR RESEARCH

Addendum to the ISOLDE and Neutron Time-of-Flight Committee

The role of In in III-nitride ternary semiconductors

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E. Alves^{1,2}, J. P. Araújo⁴, M. Barbosa^{1,4}, J. G. Correia^{1,2,6}, K. Johnston^{5,6}, P. Keßler³, K. Lorenz^{1,2}, S. Miranda¹, J. G. Marques^{1,2}, R. Vianden³

¹Instituto Tecnológico e Nuclear, Estrada Nacional 10, 2686-953 Sacavém, Portugal ²Centro de Física Nuclear da Universidade de Lisboa, Av. Prof. Gama Pinto 2,

1649-003 Lisboa, Portugal

³Helmholtz Institut für Strahlen- und Kernphysik, University of Bonn, Nussallee 14-16, 53115 Bonn, Germany

⁴Departamento de Física, Faculdade de Ciências da Universidade do Porto, 4169-007 Porto, Portugal ⁵Technische Physik, Universität des Saarlandes, Building E2.6, P.O. Box 151150, 66041 Saarbrücken, Germany

⁶PH dept, CERN, 1211 Geneva 23, Switzerland

Spokesperson(s):

K. Lorenz (Lorenz@itn.pt), R. Vianden (vianden@hiskp.uni-bonn.de) Local contact:

J. G. Correia (Guilherme.Correia@cern.ch)

Abstract

The present addendum to project IS481 will allow accomplishing the work of the running project which was not possible due to technical problems. Furthermore, the scope of the project will be extended from binary GaN and AIN to ternary AIGaN semiconductors. $\beta-\gamma$ Perturbed Angular Correlation (PAC) measurements using the ¹¹⁵Cd(¹¹⁵In) probe in GaN will allow the determination of the sign of the quadrupole interaction, an important parameter when comparing experimental results with density functional calculations of the electric field gradient. $\gamma-\gamma$ PAC using the probes ^{111m}Cd(¹¹¹Cd) and ¹¹⁷Cd(¹¹⁷In) will be used to investigate AIGaN ternaries. Special focus will lie on the investigation of implantation damage and alloy disorder. The presence and characteristics of In-V_N complexes in these alloys will be studied and compared to our previous results in binary nitrides.

Requested shifts: 12 shifts, (split into two runs over one year)

1. Introduction

Due to their wide and direct band gaps, group-III nitrides are promising semiconductor materials for a wide range of technological applications in optoelectronics, as well as high power- high frequency- and high temperature electronic devices^{1,ii}. These devices usually consist of heterostructures composed of binary (AIN, GaN, InN), ternary (InGaN, AIGaN, AIInN) or even quaternary layers. Despite the successful commercialization in particular of InGaN based photonic devices many basic questions on the mechanisms of light emission remain unanswered. A subject of intensive scientific discussion is the fact that the intense luminescence from InGaN based LEDs and laser diodes is relatively insensitive to the large density of defects, mainly threading dislocations¹¹¹. A widely accepted explanation for this behaviour is the localization of excitons at regions with minima in the potential caused for example by compositional fluctuations. This effect seems to be especially effective in Incontaining III-nitride alloys, however, the nature of the exciton trap is still unknown¹¹².

2. Project results

The present project, running since 2009, aims to understand the role of In in III-nitride alloys by investigating its immediate lattice surroundings in different III-nitride hosts. The Perturbed Angular Correlation (PAC) technique provides a powerful tool to examine the lattice environment of a substitutional In probe on a microscopic scale. Previous studies with the PAC-probe ¹¹¹In(¹¹¹Cd) in GaN and AIN revealed an unexpected, reversible behaviour of its local structure with temperature^{v,vi,vii}. After implantation and annealing GaN and AIN at 1000°C only a fraction of the In probes was found in undisturbed substitutional cation sites while a large fraction is subjected to a strong electric field gradient typical for a point defect trapped at the probe atom. However, when the measurements were performed at higher temperature the undisturbed substitutional fraction increased until all probes are found in regular sites. Surprisingly, this behaviour is fully reversible when the temperature is decreased again.

These results suggested that a large fraction of In impurities in GaN and AIN form a stable complex with a nearest neighbour nitrogen vacancy in the <0001> position. However, at the start of the present project it was not clear if the fact that the actual PAC measurement is performed at the Cd daughter nucleus and if after effects^{*} influence the PAC measurements using the ¹¹¹In(¹¹¹Cd)</sup> probe. Therefore, PAC measurements using the ^{111m}Cd(¹¹¹Cd) and ¹¹⁷Cd(¹¹⁷In) probes were performed in GaN and AIN. It was shown that the defect complex is absent for the ¹¹⁷Cd(¹¹⁷In) and ^{111m}Cd(¹¹¹Cd)</sup> probes. Therefore a peculiarity of In in III-nitride alloys. Furthermore, by performing e⁻ γ PAC measurements using the ^{111m}Cd probe it was shown that after effects are not likely to influence the measurements at the analysed temperature down to 15 K^{viii}.

A third objective of the project could not be accomplished due to technical difficulties. The aim was to determine the *sign* of the quadrupole interaction by means of a β - γ measurement using the ¹¹⁵Cd or the ¹¹¹Ag probes. In a first try, the sample implanted at ISOLDE with ¹¹⁵Cd could not be shipped to the University of Bonn in due time to perform the measurements. Therefore, in a second tentative the longer lived ¹¹¹Ag isotope was implanted. This isotope, however, was found to diffuse out of the sample during the necessary post-implant annealing treatment.

^{*} Disturbances of the probe's electronic shell are caused by the decay of ¹¹¹In to ¹¹¹Cd via electron capture. The hole in the electron shell will be filled by x-ray and Auger processes leaving further holes and excited states that cause fluctuating field gradients. In some insulators, where the recombination processes are slow due to the low electron mobility, this was seen to cause the loss of angular correlation, however, in semiconductors usually the holes are filled in a short time interval within the time resolution of the spectrometer and therefore do not interfere with the measurement.

In this addendum to the present project we ask for beam time to repeat the ¹¹⁵Cd implantation for β - γ measurement. Furthermore we would like to extend the project from binary alloys to ternary AlGaN alloys. Preliminary measurements of this material showed that PAC is a useful technique to study the effect of implantation on crystal quality and to investigate alloy disorder^{ix}.

3. Proposed work

3.1 β - γ measurements using ¹¹⁵Cd(¹¹⁵In) in GaN

The use of the probe ¹¹⁵Cd(¹¹⁵In) will allow the determination of the sign of the quadrupole interaction by means of a β - γ measurement. Although the half life of the intermediate state of this nucleus is much shorter than that of the comparable states in ¹¹¹Cd and ¹¹⁷In, with the information gained by the previous studies, it should be possible to extract the necessary information. This would be very important since, at present, density functional calculations of the electric field gradient (EFG) in the nitride semiconductors are hampered by the fact that the value of the u-parameter (u=b/c where b is the bond-length in the c-direction and c the lattice parameter) is not known with sufficient precision neither in GaN nor in AIN. Variations of the u-parameter within the experimental errors cause even the sign of the numerical EFG result to change, rendering any calculations uncertain at present.

A mobile beta detector has been set-up in Bonn for these measurements which can be moved to ISOLDE to perform the ¹¹⁵Cd measurements in order to avoid the shipping procedure.

3.2 $\gamma - \gamma$ measurements using ^{111m}Cd(¹¹¹Cd) and ¹¹⁷Cd(¹¹⁷In) in AlGaN alloys

PAC measurements with the probes ^{111m}Cd(¹¹¹Cd) and ¹¹⁷Cd(¹¹⁷In) will be performed in $AI_xGa_{1-x}N$ alloys within the entire compositional range ($0 \le x \le 1$). Residual implantation damage and alloy disorder will cause a damping of the observed PAC frequency. Furthermore, complementary measurements with the ¹¹¹In probe will be performed to check if the typical Indefect complex seen in AIN and GaN is also present in the ternary and to study how the corresponding PAC frequency and the fraction of probes trapping a defect change with composition.

Summary of requested shifts:

We estimate the total amount of ISOLDE beam time needed to accomplish the abovedescribed tasks to be 12 shifts, distributed according to table I:

Required isotope	Implanted beam	PAC experiment	Intensity [at/μC]	Target / Ion source	Comments	nº of shifts
^{111m} Cd	^{111m} Cd	γ–γ, e ⁻ –γ	10 ⁸	molten Sn, plasma		6
¹¹⁷ Cd	¹¹⁷ Ag	γ-γ	10 ⁸		Nb or Ta ion source	3
¹¹⁵ Cd	¹¹⁵ Ag	β–γ	10 ⁸	UC ₂ , RILIS (Ag)	cavity to decrease In surface ionization contamination	3

Table I: Beam time request

All of our beam times consist of collections to be measured off-line and can in this way be easily shared with other users. We stress the particular case of the ^{111m}Cd beam time, where collections should run day and night with a period of about 4-5 hours between collections that usually last for 15-30 min. There are actually four PAC setups co-shared during beam times and the samples can be implanted on the same collective sample holder used with other users which are also doing PAC experiments.

For these PAC experiments, the number of implanted atoms per sample range from $5 \cdot 10^8$ up to 10^{11} , depending on half-lives, coincidence efficiency and on the fluence limit for proper recovery of the implantation damage. All isotopes will be collected in the general-purpose implantation chambers at GLM and/or High Voltage Platform at the ISOLDE hall, building 170. All $\gamma - \gamma$ PAC measurements will be performed off-line, outside the ISOLDE hall, in the new Solid State Laboratory in building 115.

Several furnace systems exist already at ISOLDE for annealing treatments under vacuum or gas flow at atmospheric pressure at the new SSP lab.

References:

^{III} See the special issue of the Philosophical Magazine for a "snapshot of the debate": R. A. Oliver and B. Daudin, "Intentional and unintentional localization in InGaN",

Philosophical Magazine, Vol. 87, No. 13, 1 May 2007, 1967–1969.

^{iv} S. F. Chichibu et al., nature materials 5, 810 (2006).

^v K. Lorenz, F. Ruske, and R. Vianden, Appl. Phys. Lett. 80, 4531 (2002).

^{vi} K. Lorenz and R. Vianden, Hyp. Int. 158, 273 (2004).

^{vii} J. Schmitz, J. Penner, K. Lorenz, E. Alves, and R. Vianden, physica status solidi (a) 205, 93 (2008).

^{viii} P. Kessler, K. Lorenz, S.M.C. Miranda, J.G. Correia, K. Johnston, R. Vianden, The ISOLDE Collaboration, accepted in Hyperfine interactions (2010).

^{ix} T. Geruschke, K. Lorenz, R. Vianden, Physica B 404, 4882 (2009).

¹ B. Gil, ed., in Group III nitride semiconductor compounds, physics and applications; Series on Semiconductor Science and Technology 6 (Oxford Science Publications, Oxford, 1998).

ⁱⁱ S. Nakamura, G. Fasol, The blue laser diode – GaN based light emitters and lasers, Springer Verlag (1997).

Appendix

DESCRIPTION OF THE PROPOSED EXPERIMENT

The experimental setup comprises: (name the fixed-ISOLDE installations, as well as flexible elements of the experiment)

Part of the Choose an item.	Availability	Design and manufacturing
SSP-GLM chamber	Existing	To be used without any modification
Existing equipment on the solid	Existing	\square To be used without any modification \square To be modified
state labs in building 115	New New	Standard equipment supplied by a manufacturer
- 6 detector PAC standard setups		CERN/collaboration responsible for the design and/or manufacturing
- annealing furnaces		
- glove boxes		

HAZARDS GENERATED BY THE EXPERIMENT

(if using fixed installation) Hazards named in the document relevant for the fixed SSP-GLM chamber and building 115 installations.

Additional hazards:

Hazards	SSP-GLM	Building 115	[Part 3 of the experiment/equipment]
Thermodynamic and fluid	lic		
Pressure	[pressure][Bar], [volume][I]		
Vacuum	10-6 mbar at SSP chamber 10 during collections		
Temperature	295 K, room temperature collections		
Heat transfer	-		
Thermal properties of materials	-		
Cryogenic fluid		Liquid nitrogen, 1 Bar, few litres used during the PAC measurements on appropriate dewar	
Electrical and electromag	netic		
Electricity	[voltage] [V], [current][A]		
Static electricity			
Magnetic field	[magnetic field] [T]		
Batteries			
Capacitors			
Ionizing radiation			
Target material	[material]		
Beam particle type (e, p, ions, etc)			

Doom intensity			
Beam intensity			
Beam energy	Fitsestell		
Cooling liquids	[liquid]		
Gases	[gas]		
Calibration sources:			
Open source		Sources to be measured at	
	Produced at ISOLDE 111mCd (48m)	115	
	117Cd(2.5h)		
	115Cd(53.5h)		
Sealed source		22Na sources provided by RP	
Scaled Source		services at CERN, used at 115	
Isotope	111mCd (48m)		
	117Cd(2.5h)		
	115Cd(53.5h)		
Activity	111mCd (48m) < 3 e 7 Bq		
	117Cd(2.5h) < 8 e 6 Bq		
	115Cd(53.5h) < 4 e 5 Bq		
Use of activated material:	none		
Description			
Dose rate on contact	[dose] [mSV]		
and in 10 cm distance			
Isotope			
Activity			
Non-ionizing radiation		-	
Laser	none		
UV light	none		
Microwaves (300MHz-30	none		
GHz)			
Radiofrequency (1-300MHz)	none		
Chemical			
Тохіс	[chemical agent], [quantity]		
Harmful		Acetone (ICSC: 0087),	
		ethanol (ICSC: 0044) and	
		methanol (ICSC: 0057).	
		Less than few centilitres per	
		chemical, used on cleaning samples on ventilated fume	
		hood on building 115.	
		The respective ICSC forms	
		have been printed and will be	
		handled during preparation	
		and experiments.	
CMR (carcinogens, mutagens	[chemical agent], [quantity]	- · · ·	
CMR (carcinogens, mutagens and substances toxic to	[chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction)		- · · ·	
and substances toxic to reproduction) Corrosive	[chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant	[chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant Dangerous for the	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant Dangerous for the environment	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant Dangerous for the environment Mechanical	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant Dangerous for the environment Mechanical Physical impact or	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant Dangerous for the environment Mechanical Physical impact or mechanical energy (moving	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	
and substances toxic to reproduction) Corrosive Irritant Flammable Oxidizing Explosiveness Asphyxiant Dangerous for the environment Mechanical Physical impact or	[chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity] [chemical agent], [quantity]	- · · ·	

(Sharp, rough, slippery)			
Vibration	[none]		
Vehicles and Means of	[none]		
Transport			
Noise		•	•
Frequency	[frequency],[Hz] Ambient noise at the ISOLDE Hall, building 170		
Intensity	Ambient noise at the ISOLDE Hall, building 170		
Physical			
Confined spaces	[none]		
High workplaces	[none]		
Access to high workplaces	[none]		
Obstructions in passageways	[none]		
Manual handling	All samples and sample holders are manually handled either by long tweezers to insert and extract the sample holder into and out of the SSP implantation chamber at GLM, or when manipulating the samples and sample holders inside glove boxes or fume houses on building 115 r-007	All samples and sample holders are manually handled either by long tweezers to insert and extract the sample holder into and out of the SSP implantation chamber at GLM, or when manipulating the samples and sample holders inside glove boxes or fume houses on building 115 r-007	
Poor ergonomics	[none]		

0.1 Hazard identification

3.2 Average electrical power requirements (excluding fixed ISOLDE-installation mentioned above): (make a rough estimate of the total power consumption of the additional equipment used in the experiment)

There is no additional equipment with relevant power consumption on these small-scale experiments.